Amendment to Specification

On page 2, second paragraph, line 8, please amend as follows:

In the color filter process, a positive photosensitive material efor a negative photosensitive material containing pigment was coated on the glass or conductive metal film or layer having a rectangular pattern (hereinafter referred to as "substrate"), soft-baked, exposed and developed to prepare a pattern of the desired shape. In the course of forming such fine circuit pattern, when forming a photosensitive film on the substrate, the photoresist film formed at the edge of the substrate becomes irregular when compared with the photoresist film formed at the middle of the substrate. Further, the photosensitive material coated irregularly at the edge of the substrate during soft-baking or exposing process may lead to contamination by an accumulation of photosensitive material and thus, the removal thereof is required.